

Uploading C:\Program Files\Stnexp\Queries\10080319-1.str

L2 STRUCTURE UPLOADED

=> que L2 AND L1

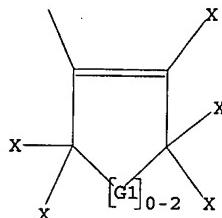
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 2067

L2 STR



G1 CF2,CBr2,CI2

Structure attributes must be viewed using STN Express query preparation.
L3 QUE ABB=ON PLU=ON L2 AND L1

=> s l3 sss sam

SAMPLE SEARCH INITIATED 11:27:34 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 91 TO ITERATE

100.0% PROCESSED 91 ITERATIONS
SEARCH TIME: 00.00.01

7 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**

PROJECTED ITERATIONS: 1248 TO 2392
PROJECTED ANSWERS: 7 TO 298

L4 7 SEA SSS SAM L2 AND L1

=> d

L4 ANSWER 1 OF 7 REGISTRY COPYRIGHT 2003 ACS on STN
RN 430427-86-4 REGISTRY

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX
NAME)

MF (C12 H18 O2 . C5 F8 . C4 H2 O3)x

CI PMS

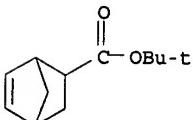
PCT Polyether, Polyvinyl

SR CA

LC STN Files: CA, CAPLUS

CM 1

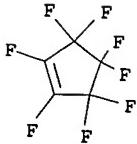
CRN 154970-45-3
CMF C12 H18 O2



CM 2

CRN 559-40-0
CMF C5 F8

STN Search



CM 3

CRN 108-31-6
CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCPLUS USPATFUL
COST IN U.S. DOLLARS

FULL ESTIMATED COST

SINCE FILE ENTRY	TOTAL SESSION
2.08	2.50

FILE 'CAPLUS' ENTERED AT 11:27:56 ON 22 SEP 2003
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FILE 'HCPLUS' ENTERED AT 11:27:56 ON 22 SEP 2003
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FILE 'USPATFULL' ENTERED AT 11:27:56 ON 22 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 14
L5 19 L4

=> s 15 and (photoresist or resist)
L6 4 L5 AND (PHOTORESIST OR RESIST)

=> d 16 1-4 ibib hitstr abs

L6 ANSWER 1 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2002:397839 CAPLUS
DOCUMENT NUMBER: 136:409059
TITLE: Fluorine-containing cycloolefin polymer,
photoresist material containing the polymer,
and formation of pattern
INVENTOR(S): Hatakeyama, Jun; Watanabe, Atsushi; Harada, Yuji;
Kawai, Yoshio; Sasako, Masaru; Endo, Masataka;
Kishimura, Shinji; Otani, Michitaka; Miyazawa, Satoru;
Tsutsumi, Kentaro; Maeda, Kazuhiko
PATENT ASSIGNEE(S): Shin-Etsu Chemical Industry Co., Ltd., Japan;
Matsushita Electric Industrial Co., Ltd.; Central
Glass Co., Ltd.
SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.

DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

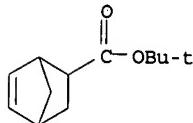
5/28/02

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002155120	A2	20020528	JP 2001-266772	20010904
PRIORITY APPLN. INFO.:			JP 2000-271209	A 20000907
IT 430427-86-4P				
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)				
(fluorine-contg. cycloolefin polymer for (chem.-amplified) pos.-working photoresist)				

RN 430427-86-4 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX
NAME)

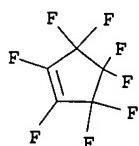
CM 1

CRN 154970-45-3
CMF C12 H18 O2



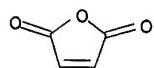
CM 2

CRN 559-40-0
CMF C5 F8

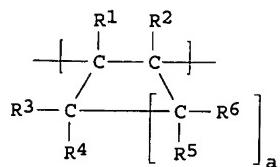


CM 3

CRN 108-31-6
CMF C4 H2 O3



GI



I

AB The polymer has a cycloolefin-derived repeating unit I (R1-R6 = H, F, Cl, C1-20 linear, branched, or cyclic alkyl, fluorinated alkyl; .gtoreq.1 of R1-R6 contain F; 0.ltoreq. a .ltoreq.10) and another repeating unit having an acid-unstable group. The photoresist contains the polymer and an org. solvent and an acid-generating agent may be further added to the compn. to give a chem.-amplified pos.-working photoresist. The compn. is applied on a substrate, heated, exposed to high energy beam at 110-190 nm or 1-15 nm wavelength through a photomask, and developed optionally after heating to give a pattern. The photoresist shows enhanced transparency to vacuum UV rays and dry etching resistance.

L6 ANSWER 2 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2001:864931 CAPLUS
DOCUMENT NUMBER: 136:12834
TITLE: Positive-working photoresist compositions
for use under vacuum UV lasers and method for pattern
formation
INVENTOR(S): Otani, Michitaka; Tsutsumi, Kentaro; Maeda, Kazuhiko

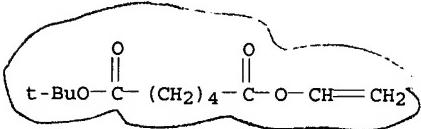
PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION: 11/30/01

11/30/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001330955	A2	20011130	JP 2000-149968	20000522
PRIORITY APPLN. INFO.:			JP 2000-149968	20000522
IT	374923-68-9P, tert-Butyl vinyl adipate-octafluorocyclopentene copolymer			
RL	IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)			
	(pos.-working perfluorocyclopentene-vinyl copolymer compns. for lithog. imaging by irradn. of vacuum UV)			
RN	374923-68-9 CAPLUS			
CN	Hexanedioic acid, 1,1-dimethylethyl ethenyl ester, polymer with octafluorocyclopentene (9CI) (CA INDEX NAME)			

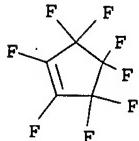
CM 1

CRN 374923-67-8
CMF C12 H20 O4

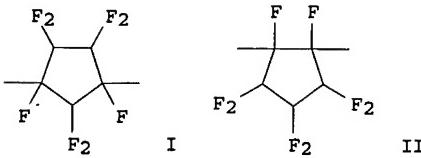


CM 2

CRN 559-40-0
CMF C5 F8



GI



AB The compns. comprise fluoropolymers which change soly against aq. alk. soln. by reaction with acids and acid generators. The polymers consist of .gtoreq.1 mol% of structural repeating units, I or II and .ltoeq.99 mol% monomers derived from vinyl compds. Preferable comonomers are also given in Markush structures. Formation of pattern is carried out by application of the compn. on a substrate, patterned exposure of the resist layer with light having wavelength 1-190 nm, and development of the irradiated layer. The compns. have high transparency against vacuum UV (VUV), esp. against F2 excimer lasers, and have high sensitivity.

L6 ANSWER 3 OF 4 HCPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 2002:397839 HCPLUS

DOCUMENT NUMBER: 136:409059

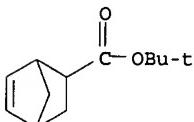
TITLE: Fluorine-containing cycloolefin polymer,
photoresist material containing the polymer,
and formation of pattern

INVENTOR(S) : Hatakeyama, Jun; Watanabe, Atsushi; Harada, Yuji;

Kawai, Yoshio; Sasako, Masaru; Endo, Masataka;
 Kishimura, Shinji; Otani, Michitaka; Miyazawa, Satoru;
 Tsutsumi, Kentaro; Maeda, Kazuhiko
PATENT ASSIGNEE(S): Shin-Etsu Chemical Industry Co., Ltd., Japan;
 Matsushita Electric Industrial Co., Ltd.; Central
 Glass Co., Ltd.
SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

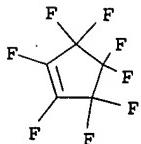
5/28/02

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002155120	A2	20020528	JP 2001-266772	20010904
PRIORITY APPLN. INFO.:			JP 2000-271209	A 20000907
IT	430427-86-4P		RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (fluorine-contg. cycloolefin polymer for (chem.-amplified) pos.-working photoresist)	
RN	430427-86-4 HCPLUS			
CN	Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX NAME)			
CM	1			
CRN	154970-45-3			
CMF	C12 H18 O2			



CM 2

CRN 559-40-0
CMF C5 F8

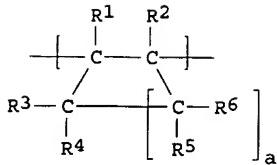


CM 3

CRN 108-31-6
CMF C4 H2 O3



GI



I

AB The polymer has a cycloolefin-derived repeating unit I (R1-R6 = H, F, Cl, Cl-20 linear, branched, or cyclic alkyl, fluorinated alkyl; .gtoreq.1 of R1-R6 contain F; 0.1toreq. a .ltoeq.10) and another repeating unit having an acid-unstable group. The photoresist contains the polymer and an org. solvent and an acid-generating agent may be further added to the compn. to give a chem.-amplified pos.-working photoresist. The compn. is applied on a substrate, heated, exposed to high energy beam at 110-190 nm or 1-15 nm wavelength through a photomask, and developed optionally after heating to give a pattern. The photoresist shows enhanced transparency to vacuum UV rays and dry etching resistance.

L6 ANSWER 4 OF 4 HCPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 2001:864931 HCPLUS

DOCUMENT NUMBER: 136:12834

TITLE: Positive-working photoresist compositions
for use under vacuum UV lasers and method for pattern formation

INVENTOR(S): Otani, Michitaka; Tsutsumi, Kentaro; Maeda, Kazuhiko
PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

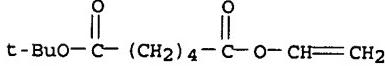
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001330955	A2	20011130	JP 2000-149968	20000522
PRIORITY APPLN. INFO.:			JP 2000-149968	20000522
IT 374923-68-9P	tert-Butyl vinyl adipate-octafluorocyclopentene copolymer			
RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)				
(pos.-working perfluorocyclopentene-vinyl copolymer compns. for lithog. imaging by irradn. of vacuum UV)				
RN 374923-68-9 HCPLUS				
CN Hexanedioic acid, 1,1-dimethylethyl ethenyl ester, polymer with octafluorocyclopentene (9CI) (CA INDEX NAME)				

CM 1

CRN 374923-67-8

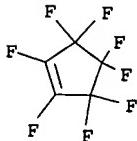
CMF C12 H20 O4

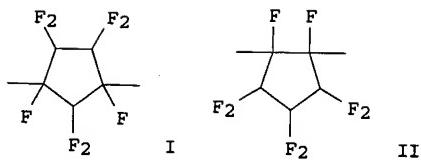


CM 2

CRN 559-40-0

CMF C5 F8



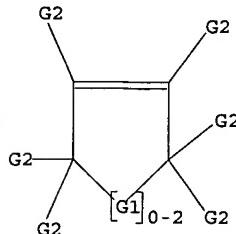


AB The compns. comprise fluoropolymers which change soly against aq. alk. soln. by reaction with acids and acid generators. The polymers consist of >0.1 mol% of structural repeating units I or II and <0.99 mol% monomers derived from vinyl compds. Preferable comonomers are also given in Markush structures. Formation of pattern is carried out by application of the compn. on a substrate, patterned exposure of the resist layer with light having wavelength 1-190 nm, and development of the irradiated layer. The compns. have high transparency against vacuum UV (VUV), esp. against F2 excimer lasers, and have high sensitivity.

PROJECTED ITERATIONS: 536511 TO 556249
PROJECTED ANSWERS: 649 TO 1535

L10 2 SEA SSS SAM L8 AND L7

=> d 19
L9 HAS NO ANSWERS
L7 SCR 2067
L8 STR



G1 CF2, CBr2, Cl2
G2 CF2, CF3, CC12, CCl3, CBr2, CBr3, CI2, CI3, Cl, Br, F, I, X

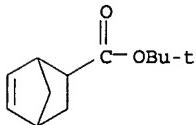
Structure attributes must be viewed using STN Express query preparation.
L9 QUE ABB=ON PLU=ON L8 AND L7

=> d 110

L10 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS on STN
RN 430427-86-4 REGISTRY
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX
NAME)
MF (C12 H18 O2 . C5 F8 . C4 H2 O3)x
CI PMS
PCT Polyether, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS

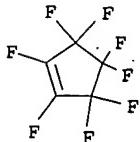
CM 1

CRN 154970-45-3
CMF C12 H18 O2



CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 108-31-6
CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
 1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFUL COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	2.08	31.49
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	0.00	-2.60

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FILE 'USPATFULL' ENTERED AT 11:32:38 ON 22 SEP 2003
 CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l10
 L11 5 L10

=> d his

(FILE 'HOME' ENTERED AT 11:26:15 ON 22 SEP 2003)

FILE 'REGISTRY' ENTERED AT 11:27:08 ON 22 SEP 2003

L1 SCREEN 2067
 L2 STRUCTURE uploaded
 L3 QUE L2 AND L1
 L4 7 S L3 SSS SAM

L5 FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 11:27:56 ON 22 SEP 2003
 19 S L4
 L6 4 S L5 AND (PHOTORESIST OR RESIST)

FILE 'HOME' ENTERED AT 11:29:06 ON 22 SEP 2003

FILE 'REGISTRY' ENTERED AT 11:31:41 ON 22 SEP 2003

L7 SCREEN 2067
 L8 STRUCTURE uploaded
 L9 QUE L8 AND L7

L10 FILE 'REGISTRY' ENTERED AT 11:32:10 ON 22 SEP 2003
 2 S L9 SSS SAM

L11 FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 11:32:38 ON 22 SEP 2003
 5 S L10

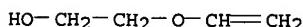
=> s l11 not 16
 L12 3 L11 NOT L6

=> d l12 1-3 ibib hitstr abs

L12 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN
 ACCESSION NUMBER: 2001:326291 CAPLUS
 DOCUMENT NUMBER: 134:341129
 TITLE: Fluoropolymers having saturated perfluoro rings with
 good solubility in organic solvents and their
 manufacture
 INVENTOR(S): Akama, Hidehiro; Sugimoto, Hiromi; Tsutsumi, Kentaro
 PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

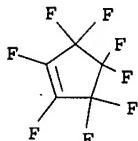
5|8|01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001122928	A2	20010508	JP 2000-232570	20000801
PRIORITY APPLN. INFO.:			JP 1999-231687	A 19990818
IT	337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer	RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)		
		(manuf. of fluoropolymers having satd. perfluoro rings with good solv. in org. solvents for transparent films)		
RN	337488-50-3 CAPLUS			
CN	Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)			
CM	1			
CRN	764-48-7			
CMF	C4 H8 O2			



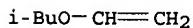
CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 109-53-5
CMF C6 H12 O



AB The fluoropolymers (av. mol. wt. 1000-1,000,000; measured by gel permeation chromatog.), useful for transparent films, coatings, etc., contain repeating units of (A) 1-99 mol% 1,3- or 1,2-perfluorocyclopentylene and (B) 1-99 mol% divalent org. groups. Thus, an acetone soln. of vinyl acetate-octafluorocyclopentene copolymer was applied on a glass plate and dried to give a transparent film.

L12 ANSWER 2 OF 3 HCPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2001:326291 HCPLUS
DOCUMENT NUMBER: 134:341129
TITLE: Fluoropolymers having saturated perfluoro rings with good solubility in organic solvents and their manufacture
INVENTOR(S): Akama, Hidehiro; Sugimoto, Hiromi; Tsutsumi, Kentaro
PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

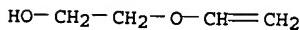
5|8|01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001122928	A2	20010508	JP 2000-232570	20000801
PRIORITY APPLN. INFO.:			JP 1999-231687	A 19990818
IT	337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer	RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)		

(manuf. of fluoropolymers having satd. perfluoro rings with good solv.
in org. solvents for transparent films)
RN 337488-50-3 HCAPLUS
CN Ethanol, 2-(ethenylloxy)-, polymer with 1-(ethenylloxy)-2-methylpropane and
octafluorocyclopentene (9CI) (CA INDEX NAME)

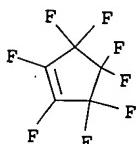
CM 1

CRN 764-48-7
CMF C4 H8 O2



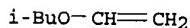
CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 109-53-5
CMF C6 H12 O



AB The fluoropolymers (av. mol. wt. 1000-1,000,000; measured by gel permeation chromatog.), useful for transparent films, coatings, etc., contain repeating units of (A) 1-99 mol% 1,3- or 1,2-perfluorocyclopentylene and (B) 1-99 mol% divalent org. groups. Thus, an acetone soln. of vinyl acetate-octafluorocyclopentene copolymer was applied on a glass plate and dried to give a transparent film.

L12 ANSWER 3 OF 3 USPATFULL on STN
ACCESSION NUMBER: 2002:137125 USPATFULL
TITLE: Fluorine-containing copolymer and composition for preparing low reflectance film
INVENTOR(S): Akama, Shuyo, Saitama, JAPAN
Sugimoto, Hiromi, Saitama, JAPAN
Tsutsumi, Kentaro, Saitama, JAPAN
PATENT ASSIGNEE(S): Central Glass Company, Limited, Ube, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6403744	B1	20020611
APPLICATION INFO.:	US 2000-640536		20000817 (9)

6/11/02

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-231687	19990818
	JP 2000-84628	20000324

8/17/00 ✓ 102(e)

DOCUMENT TYPE: Utility

FILE SEGMENT: GRANTED

PRIMARY EXAMINER: Zitomer, Fred

LEGAL REPRESENTATIVE: Crowell & Moring LLP

NUMBER OF CLAIMS: 19

EXEMPLARY CLAIM: 1

NUMBER OF DRAWINGS: 6 Drawing Figure(s); 6 Drawing Page(s)

LINE COUNT: 954

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

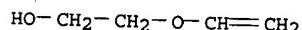
IT 337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer
(manuf. of fluoropolymers having satd. perfluoro rings with good solv.
in org. solvents for transparent films)

RN 337488-50-3 USPATFULL

CN Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and
octafluorocyclopentene (9CI) (CA INDEX NAME)

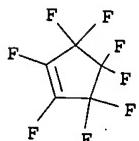
CM 1

CRN 764-48-7
CMF C4 H8 O2



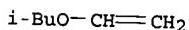
CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 109-53-5
CMF C6 H12 O



AB The invention relates to a fluorine-containing copolymer. This copolymer contains 1-99 mol % of a special first repeating unit of a cyclic perfluoro group; and 99-1 mol % of a second repeating unit of a bivalent organic group. The copolymer has a number average molecular weight of from 1,000 to 1,000,000 determined in a gel permeation chromatography using polystyrene as a standard material thereof. The invention further relates to a composition for forming a low reflectance film. This composition contains as a film-forming component a fluorine-containing polymer containing the first repeating unit. This polymer can be the above copolymer. A film formed by applying the composition to a substrate provides low reflectance and is improved in hardness.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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=> file reg
COST IN U.S. DOLLARS
          SINCE FILE      TOTAL
          ENTRY        SESSION
FULL ESTIMATED COST           0.21      0.21
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FILE 'REGISTRY' ENTERED AT 11:34:17 ON 22 SEP 2003
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Property values tagged with IC are from the ZIC/VINITI data file
 provided by InfoChem.

STRUCTURE FILE UPDATES: 21 SEP 2003 HIGHEST RN 590345-44-1
 DICTIONARY FILE UPDATES: 21 SEP 2003 HIGHEST RN 590345-44-1

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003

Please note that search-term pricing does apply when
 conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details:
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

```
=> s octafluorocyclopentene
      0 OCTAFLUOROCYCLOCOPENTENE
L1      0 OCTAFLUOROCYCLOCOPENTENE
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```
=> s octafluoropentane
L2      41 OCTAFLUOROPENTANE
```

```
=> s hexafluorocyclopentene
L3      20 HEXAFLUOROCYCLOCOPENTENE
```

```
=> s hexafluorocyclobutene
L4      15 HEXAFLUOROCYCLOBUTENE
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=> s octafluorocyclopentene
L5      37 OCTAFLUOROCYCLOCOPENTENE
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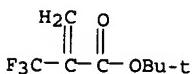
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=> s 12 or 14 or 15
L6      90 L2 OR L4 OR L5
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=> d

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L6  ANSWER 1 OF 90  REGISTRY  COPYRIGHT 2003 ACS on STN
RN  568587-28-0  REGISTRY
CN  2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester,
    polymer with (ethenyl)oxy)cyclohexane, octafluorocyclopentene and
    2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate
    (9CI)  (CA INDEX NAME)
MF  (C8 H14 O . C8 H11 F3 O2 . C7 H3 F9 O2 . C5 F8)x
CI  PMS
PCT Polyacrylic, Polyether, Polyvinyl
SR  CA
LC  STN Files: CA, CAPLUS
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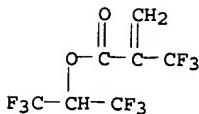
CM 1

CRN 105935-24-8
 CMF C8 H11 F3 O2



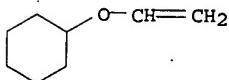
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CRN 91520-41-1
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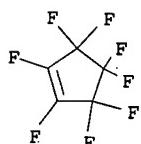
CM 3

CRN 2182-55-0
CMF C8 H14 O



CM 4

CRN 559-40-0
CMF C5 F8



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFUL	SINCE FILE	TOTAL
COST IN U.S. DOLLARS	ENTRY	SESSION
FULL ESTIMATED COST	23.98	24.19

FILE 'CAPLUS' ENTERED AT 11:35:57 ON 22 SEP 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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FILE 'HCAPLUS' ENTERED AT 11:35:57 ON 22 SEP 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 11:35:57 ON 22 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 16
L7 1620 L6

=> s 17 and (photoresist or resist)
L8 143 L7 AND (PHOTORESIST OR RESIST)

=> s 18 and (?acid (w) generator)
L9 15 L8 AND (?ACID (W) GENERATOR)

=> s 19 and solvent
L10 7 L9 AND SOLVENT

=> duplicates remove l10
DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L10
L11 3 DUPLICATE REMOVE L10 (4 DUPLICATES REMOVED)

=> d 111 1-3 ibib hitstr

L11 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2003:77400 CAPLUS

DOCUMENT NUMBER: 138:145061
 TITLE: Photoresist monomers, polymers thereof and
 photoresist compositions containing the same
 INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
 PATENT ASSIGNEE(S): S. Korea
 SOURCE: U.S. Pat. Appl. Publ., 12 pp.
 CODEN: USXXCO

DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE
 US 2003022101 A1 20030130 US 2002-80319 20020221
 PRIORITY APPLN. INFO.: KR 2001-38026 A 20010629

OTHER SOURCE(S): MARPAT 138:145061

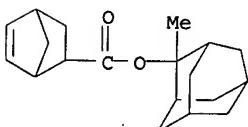
IT 492469-83-7P 492469-85-9P 492469-88-2DP,
 4-Acetoxystyrene-hexafluorocyclobutene copolymer, hydrolyzed and reaction
 product with ethylvinylether
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (photoresist monomers and polymers for photoresist
 compns.)

RN 492469-83-7 CAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-
 methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with
 hexafluorocyclobutene (9CI) (CA INDEX NAME)

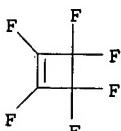
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CRN 328087-85-0
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CM 2

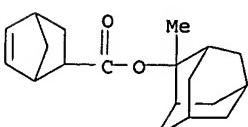
CRN 697-11-0
 CMF C4 F6



RN 492469-85-9 CAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-
 methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with
 2-ethyltricyclo[3.3.1.13,7]dec-2-yl 2-propenoate and
 octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 328087-85-0
 CMF C19 H26 O2



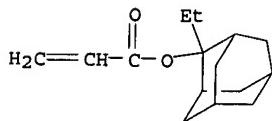
CM 2

1/30/03

2/21/02

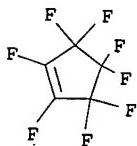
present application

CRN 303186-14-3
CMF C15 H22 O2



CM 3

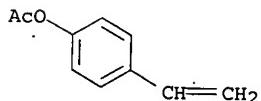
CRN 559-40-0
CMF C5 F8



RN 492469-88-2 CAPLUS
CN Phenol, 4-ethenyl-, acetate, polymer with hexafluorocyclobutene (9CI) (CA INDEX NAME)

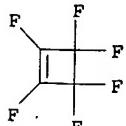
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CRN 2628-16-2
CMF C10 H10 O2



CM 2

CRN 697-11-0
CMF C4 F6



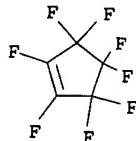
L11 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2003:5311 CAPLUS
DOCUMENT NUMBER: 138:63829
TITLE: Photoresist monomers, polymers thereof and photoresist compositions containing the same
INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
PATENT ASSIGNEE(S): S. Korea
SOURCE: U.S. Pat. Appl. Publ., 13 pp
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

Not to another!

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003003379	A1	20030102	US 2002-79348	20020220
JP 2003040931	A2	20030213	JP 2002-122435	20020424

2/20/02

PRIORITY APPLN. INFO.: KR 2001-34603 A 20010619
IT 559-40-0 RL: RCT (Reactant); RACT (Reactant or reagent)
(Repn. fluoropolymer for photoresist compns.)
RN 559-40-0 CAPLUS
CN Cyclopentene, octafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



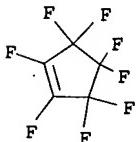
L11 ANSWER 3 OF 3 USPATFULL on STN
ACCESSION NUMBER: 2003:10537 USPATFULL
TITLE: Polymers, resist compositions and patterning process
INVENTOR(S): Harada, Yuji, Nakakubiki-gun, JAPAN
Watanabe, Jun, Nakakubiki-gun, JAPAN
Hatakeyama, Jun, Nakakubiki-gun, JAPAN
Kawai, Yoshio, Nakakubiki-gun, JAPAN
Sasago, Masaru, Hirakata-shi, JAPAN
Endo, Masayuki, Izumi-shi, JAPAN
Kishimura, Shinji, Itami-shi, JAPAN
Ootani, Michitaka, Kawagoe-shi, JAPAN
Miyazawa, Satoru, Kawagoe-shi, JAPAN
Tsutsumi, Kentaro, Kawagoe-shi, JAPAN
Maeda, Kazuhiko, Chiyoda-ku, JAPAN
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003008231	A1	20030109
APPLICATION INFO.:	US 2002-84828	A1	20020228 (10)

2/28/02

WT prior art

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-53664	20010228
	JP 2001-53669	20010228
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	9	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1461	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT 559-40-0, Octafluorocyclopentene	(F-contg. group-contg. polymers for chem. amplified pos.-working resists and their use in pattern formation)	
RN 559-40-0 USPATFULL		
CN Cyclopentene, octafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)		



=> d 120 1-3 ibib hitstr

L20 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2003:626408 CAPLUS
DOCUMENT NUMBER: 139:157393
TITLE: Fluorine-containing photoresist with
reaction anchor for chemical amplification and
improved copolymerization characteristics
INVENTOR(S): Rottstegge, Joerg
PATENT ASSIGNEE(S): Infineon Technologies A.-G., Germany
SOURCE: Ger. Offen., 14 pp.
CODEN: GWXXBX
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

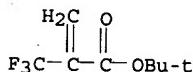
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 10203838	A1	20030814	DE 2002-10203838	20020131
US 2003157432	A1	20030821	US 2003-356791	20030131
PRIORITY APPLN. INFO.:			DE 2002-10203838 A	20020131

IT 572922-00-0P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(fluorine-contg. photoresist with reaction anchor for chem.
amplification and improved copolymn. characteristics)

RN 572922-00-0 CAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer
with decafluorocyclohexene and 3a,4,7,7a-tetrahydro-1,3-isobenzofurandione
(9CI) (CA INDEX NAME)

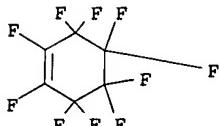
CM 1

CRN 105935-24-8
CMF C8 H11 F3 O2



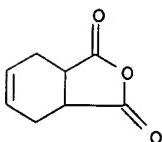
CM 2

CRN 355-75-9
CMF C6 F10



CM 3

CRN 85-43-8
CMF C8 H8 O3



L20 ANSWER 2 OF 3 USPATFULL on STN
ACCESSION NUMBER: 2003:225620 USPATFULL
TITLE: Fluorine-containing photoresist having
reactive anchors for chemical amplification and

INVENTOR(S): improved copolymerization properties
Rottstegge, Jorg, Lilienthal, GERMANY, FEDERAL REPUBLIC
OF

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003157432	A1	20030821
APPLICATION INFO.:	US 2003-356791	A1	20030131 (10)

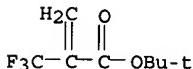
	NUMBER	DATE
PRIORITY INFORMATION:	DE 2002-10203838	20020131
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	LERNER AND GREENBERG, P.A., POST OFFICE BOX 2480, HOLLYWOOD, FL, 33022-2480	
NUMBER OF CLAIMS:	14	
EXEMPLARY CLAIM:	1	
LINE COUNT:	871	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 572922-00-0P
(fluorine-contg. photoresist with reaction anchor for chem.
amplification and improved copolyrn. characteristics)

RN 572922-00-0 USPATFULL
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer
with decafluoroclohexene and 3a,4,7,7a-tetrahydro-1,3-
isobenzofurandione (9CI) (CA INDEX NAME)

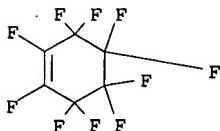
CM 1

CRN 105935-24-8
CMF C8 H11 F3 O2



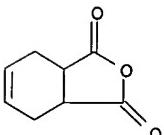
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CRN 355-75-9
CMF C6 F10



CM 3

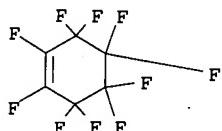
CRN 85-43-8
CMF C8 H8 O3



L20 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2002:868986 CAPLUS
DOCUMENT NUMBER: 137:370796
TITLE: Radiation-sensitive polysiloxane resin composition
INVENTOR(S): Iwasawa, Haruo; Hayashi, Akihiro; Shimokawa, Tsutomu;
Yamamoto, Masafumi
PATENT ASSIGNEE(S): JSR Co., Ltd., Japan
SOURCE: PCT Int. Appl., 155 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent

LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002090423	A1	20021114	WO 2002-JP4333	20020430
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
JP 2003020335	A2	20030124	JP 2002-48643	20020225
PRIORITY APPLN. INFO.:			JP 2001-133795	A 20010501
			JP 2002-48643	A 20020225
OTHER SOURCE(S):		MARPAT 137:370796		
IT	355-75-9, Decafluorocyclohexene			
RL	RCT (Reactant); RACT (Reactant or reagent) (radiation-sensitive polysiloxane resin compn.)			
RN	355-75-9 CAPLUS			
CN	Cyclohexene, decafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)			



REFERENCE COUNT: 25 THERE ARE 25 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

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